

### **AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

#### **LISTING OF CLAIMS:**

1. (Currently Amended): An optical interference display, at least comprising:  
a deformable electrode; and  
a light-incidence electrode, wherein the deformable electrode and light-incidence electrode are supported by post, the light-incidence electrode comprising:  
a conductive transparent layer; and  
a dielectric layer located on the conductive transparent layer, wherein a incident light irradiate form a side of the conductive transparent layer, ~~the~~ a material of the conductive transparent layer ~~and a thickness of the conductive transparent layer absorb~~ absorbs at least 30 % of the incident light.
2. (Original): The optical interference display of claim 1, wherein a material of the conductive transparent layer is selected from the group consisting of ITO, IZO, ZO, IO and the combination thereof.
3. (Original): The optical interference display of claim 1, wherein a material of the dielectric layer comprises silicon oxide, silicon nitride or metal oxide.
4. (Original): The optical interference display of claim 1, wherein lattice of the conductive transparent layer is disordered.
5. (Currently Amended): The optical interference display of claim 1, wherein the material has axes different direction of -axis of in every part of the conductive transparent layer are different or impurities.
6. (Original): The optical interference display of claim 1, wherein the conductive transparent layer further comprises more than 100ppm impurity.

7. (Currently Amended): An optical interference display plate, at least comprising:  
a deformable electrode; and  
a light-incidence electrode, wherein the deformable electrode and light-incidence electrode are supported by post, the light-incidence electrode comprising:  
two a first conductive transparent layerslayer;  
a first dielectric layer located on the first conductive layer;  
a second conductive layer located on the first dielectric layer; and  
two a second dielectric layers-layer located on the second conductive layer, each of the dielectric layers located on each of the conductive transparent layers, wherein a incident light irradiate form a side of the conductive transparent layer, the material of the conductive transparent layer and a thickness of the conductive transparent layer absorb at least 30 % of the incident light.

8. (Currently Amended): The optical interference display of claim 7, wherein a material of the first and the second conductive transparent layer-layers is selected from the group consisting of ITO, IZO, ZO, IO and the combination thereof.

9. (Currently Amended): The optical interference display of claim 7, wherein a material of the first and the second dielectric layer-layers comprises silicon oxide, silicon nitride or metal oxide.

10. (Currently Amended): The optical interference display of claim 7, wherein an orientation of the lattice of the first conductive transparent layer and an orientation of the lattice of the second conductive transparent layer is are disordered different.

11. (Currently Amended): The optical interference display of claim 7, wherein directions of axes-axis of every part of the first conductive transparent layer and the second conductive layer are different.

12. (Currently Amended): The optical interference display plate structure of claim 7, wherein the first conductive transparent layer and the second conductive transparent layer further comprises more than 100ppm impurity.

13. (Currently Amended): An optical interference display plate, at least comprising:  
a deformable electrode; and  
a light-incidence electrode, wherein the deformable electrode and light-incidence  
electrode are supported by post, the light-incidence electrode comprising:

- a first conductive transparent layer;
- a first dielectric layer located on the first conductive transparent layer;
- a second conductive transparent layer located on the first dielectric layer;
- a second dielectric layer located on the second conductive transparent layer;
- a third conductive transparent layer located on the second dielectric layer; and

a third dielectric layer located on the third conductive transparent layer,

wherein an incident light irradiates from a side of the first conductive transparent layer, the material of the first conductive transparent layer, the second conductive transparent layer, the third conductive transparent layer and a thickness of the first conductive transparent layer, the second conductive transparent layer, the third conductive transparent layer absorb at least 30 % of the incident light.

14. (Original): The optical interference display of claim 13, wherein a material of the first conductive transparent layer, the second conductive transparent layer and the third conductive transparent layer is selected from the group consisting of ITO, IZO, ZO, IO and the combination thereof.

15. (Original): The optical interference display of claim 13, wherein a material of the first dielectric layer, the second dielectric layer and the third dielectric layer comprises silicon oxide, silicon nitride or metal oxide.

16. (Currently Amended): The optical interference display of claim 13, wherein the orientation of the lattice of the first conductive transparent layer and orientation of the lattice of the second conductive transparent layer ~~is~~ are different.

17. (Currently Amended): The optical interference display of claim 13, wherein the orientation of the lattice of the second conductive transparent layer and orientation of the lattice of the third conductive transparent layer ~~is~~ are different.

Amendment under 37 C.F.R. § 1.111  
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18. (Currently Amended): The optical interference display of claim 13, wherein a direction of an axis of the first conductive transparent layer and a direction of an axis of the second conductive transparent layer ~~is different~~ is are different.

19. (Currently Amended): The optical interference display of claim 13, wherein a direction of an axis of the second conductive transparent layer and a direction of an axis of the third conductive transparent layer ~~is different~~ is are different.

20. (Currently Amended): The optical interference display plate structure of claim 13, wherein the conductive transparent layers further comprises more than 100ppm impurity.